

## Answers to Reviewer 3

Dear Reviewer,

Thank you very much for your comments and suggestions. The manuscript was now improved, all the changes in the manuscript being made by using the *Track changes* function of MS Word. Please find below our point-to-point answers to your comments.

1. Please extend part “Methods of analysis”. For example what kind of AFM mode and cantilever have been used to analyze specific surface.

We added more details on the AFM description: "... AFM contact mode, cantilever n<sup>+</sup> - silicon with resistivity 0.01-0.02 Ωcm, thickness 2±1 μm and force constant 0.02-0.77 N/m."

2. The same situation in case of SEM and EDS – general description should be extend.

Details were added on the SEM-EDS description:

“For electron spectroscopy a SE detector was used at 30 kV filament supply and a working distance of 15.5 mm. Bruker detector X-Flash 6/30 with Automatic mode detection, precise experiment was used for EDX analysis.”

3. Maybe xps measurements may be helpfull.

The samples are no longer suitable for more analyzes, after material was collected for FTIR.

4. The profile scan line in Fig 7b should be marked on an image 7c.

The profile scan was marked on the image 7c.

5. Please in a detail explain parts of Figure 8.

Figure 8 was explained in detail.

6. Please in Figure 9 mark zoomed fragment, any suggestion of a crystalline form?

We added in the revised text as it follows:

“The crystal structure in Figure 9b belongs to the components resulted from reaction between RB21 and  $\text{NaHCO}_3$  in the aqueous solution poured on the silver thin film.”

7. Fig 12 – what is the size of observed area?

We added in the revised text as it follows:

“The size of the observed area is of 1.4 x 1.1 mm as can be measured on the grid of 0.1 x 0.1 mm attached with the image of the thin film.”

On behalf of all authors,

Prof. Dan-Gheorghe Dimitriu